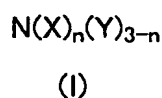


In the Claims:

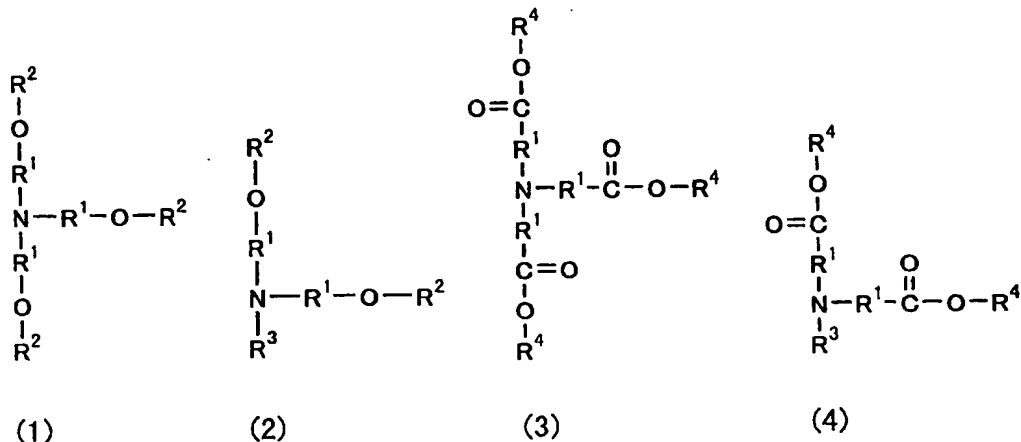
1. (Original) A resist composition comprising one or more basic compounds selected from those represented by the following formula (I):



wherein, n stands for 1, 2 or 3; side chains Xs are the same or different and each independently represents $-\text{R}^1-\text{O}-\text{R}^2$ or $-\text{R}^1-\text{C}(=\text{O})-\text{O}-\text{R}^{61}$, in which R^1 's are the same or different and each independently represents an alkylene group of 1 to 5 carbon atoms, R^2 's are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms containing a carbonyl or ester group, and R^{61} 's are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a carbonyl group, an ester group, an ether group, a hydroxyl group or a lactone ring, or R^1 and R^2 , or R^1 and R^{61} in the same side chain may be coupled together to form a ring; and side chains Ys are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain an ether or hydroxyl group.

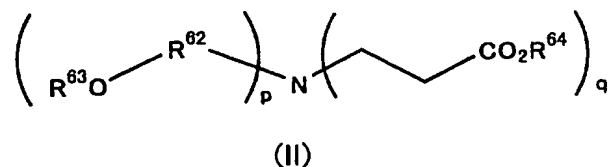
2. (Original) A resist composition according to claim 1, wherein n in the formula (I) stands for 1 or 2.

3. (Original) A resist composition comprising one or more basic compounds selected from those represented by the following formulas (1) to (4).



wherein, R^1 's are the same or different and each independently represents a C_{1-5} alkylene group, R^2 's are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms containing a carbonyl group or an ester group, R^3 represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxyl or ether group, and R^4 's are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a carbonyl, ester or ether group.

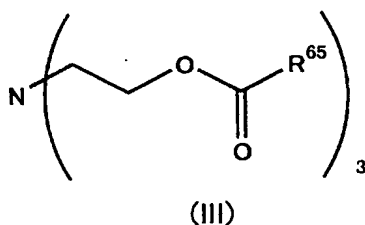
4. (Original) A resist composition comprising one or more basic compounds selected from those represented by the following formula (II):



wherein, R^{62} represents a linear or branched alkylene group of 1 to 5 carbon atoms, p stands for 0, 1 or 2 with the proviso that $p+q=3$, R^{63} 's are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 15 carbon atoms which may contain an ether, carbonyl, ester or hydroxyl group and R^{64} 's are

the same or different and each independently represents a linear, branched or cyclic alkyl group which may contain a carbonyl group, an ester group, an ether group, a hydroxyl group or a lactone ring.

5. (Original) A resist composition comprising one or more basic compounds selected from those represented by the following formula (III):



wherein R^{65} s are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 15 carbon atoms which may contain an ether, carbonyl, ester or hydroxyl group.

6. (Cancelled)

7. (Original) A resist composition according to claim 2, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

8. (Cancelled)

9. (Original) A resist composition according to claim 4, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

10. (Cancelled)

11. (Cancelled)

12. (Original) A resist composition according to claim 7, further comprising a dissolution inhibitor.

13. (Cancelled)

14. (Original) A resist composition according to claim 9, further comprising a dissolution inhibitor.

15. (Cancelled)

16. (Cancelled)

17. (Original) A resist composition according to claim 2, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.

18. (Cancelled)

19. (Original) A resist composition according to claim 4, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.

In re: Hatakeyama et al.
Serial No.: 10/615,683
Filed: July 9, 2003
Page 6 of 7

20. (Cancelled)